

IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. *(Previously Presented)* A lithographic apparatus comprising:
 - an illumination system configured to provide a beam of radiation;
 - a support structure constructed to support a patterning device, said patterning device configured to impart said beam of radiation with a desired pattern in its cross-section;
 - a substrate holder configured to hold a substrate;
 - a projection system configured to project said patterned beam onto a target portion of said substrate;
 - a conditioned chamber;
 - an actuator configured to introduce at least one of said patterning device and said substrate into said conditioned chamber;
 - a carrier structure, coupled to said actuator, configured to support said at least one of said patterning device and said substrate during the introduction into said conditioned chamber; and
 - an alignment system, disposed outside said conditioned chamber, configured to position said at least one of said patterning device and said substrate in alignment with said projected patterned beam of radiation by determining position and orientation of said at least one of said patterning device and said substrate relative to a reference point on said carrier structure and adjusting said position and orientation of said at least one of said patterning device and said substrate in accordance with said reference point.
2. *(Previously Presented)* The lithographic apparatus of Claim 1, wherein said actuator includes an actuator arm that is coupled to said carrier structure, which is configured to move said at least one of said patterning device and said substrate from said alignment system to said support structure or substrate holder within said conditioned chamber, respectively.

3. (Original) The lithographic apparatus of Claim 2, wherein said carrier structure is provided with a fixation device configured to fix said at least one of said patterning device and said substrate to said carrier structure.

4. (Original) The lithographic apparatus of Claim 2, wherein said alignment system is provided with a docking system configured to dock said carrier structure.

5. (Original) The lithographic apparatus of Claim 2, wherein said at least one of said patterning device and said substrate is provided with a docking system configured to dock said carrier structure.

6. (Original) The lithographic apparatus of Claim 1, wherein said conditioned chamber comprises a reduced pressure environment.

7. (Original) The lithographic apparatus of Claim 1, wherein said conditioned chamber comprises a reduced particle concentration environment.

8. (Previously Presented) A device manufacturing method comprising:
providing a substrate;
providing a beam of radiation;
providing a patterning device;
placing at least one of said substrate and said patterning device onto a carrier structure;

aligning said at least one of said substrate and said patterning device with said beam of radiation outside of a conditioned chamber by:

(a) determining position and orientation of said at least one of said patterning device and said substrate relative to a reference point on said carrier structure, and

(b) adjusting said position and orientation of said at least one of said patterning device and said substrate in accordance with said reference point;

introducing said at least one of said substrate and said patterning device into a conditioned chamber;

configuring said beam of radiation with a desired pattern in its cross-section based on said patterning device;

projecting said patterned beam of radiation onto a target portion of said substrate.

9. *(Previously Presented)* The device manufacturing method of Claim 8, wherein said introducing comprises actuating said carrier structure to support and move said at least one of said patterning device and said substrate from an alignment system to a support structure or a substrate holder contained within said conditioned chamber, respectively.

10. *(Original)* The device manufacturing method of Claim 9, further including securing said at least one of said patterning device and said substrate to said carrier structure.

11. *(Original)* The device manufacturing method of Claim 9, wherein said aligning includes docking said carrier structure with a docking system.

12. *(Original)* The device manufacturing method of Claim 9, further including providing said at least one of said patterning device and said substrate with a docking system configured to dock said carrier structure.

13. *(Original)* The device manufacturing method of Claim 8, wherein said conditioned chamber comprises a reduced pressure environment.

14. *(Original)* The device manufacturing method of Claim 8, wherein said conditioned chamber comprises a reduced particle concentration environment.

15. *(Previously Presented)* A lithographic apparatus comprising:
- a patterning device configured to impart a beam of radiation with a desired pattern in its cross-section, said patterning device being supported by a support structure;
 - a projection system configured to project said patterned beam onto a target portion of a substrate;
 - a conditioned chamber that houses said support structure;
 - an actuator configured to introduce said patterning device into said conditioned chamber; and
 - an alignment system, disposed outside said conditioned chamber, to align said patterning device with said projected patterned beam of radiation by:
 - (a) determining position and orientation of said patterning device relative to a reference point on a carrier structure that supports said patterning device during the introduction of said patterning device into said conditioned chamber, and
 - (b) adjusting said position and orientation of said patterning device based on said reference point.
16. *(Previously Presented)* The lithographic apparatus of Claim 15, wherein said actuator includes an actuator arm having a carrier structure, said carrier structure configured to support and move said patterning device and said substrate from said alignment system to said support structure.
17. *(Previously Presented)* The lithographic apparatus of Claim 16, wherein said carrier structure is provided with a fixation device configured to secure said patterning device to said carrier structure.
18. *(Original)* The lithographic apparatus of Claim 16, wherein said alignment system is provided with a docking system configured to dock said carrier structure.

19. *(Previously Presented)* The lithographic apparatus of Claim 16, wherein said patterning device is provided with a docking system configured to dock said carrier structure.

20. *(Original)* The lithographic apparatus of Claim 15, wherein said conditioned chamber comprises a reduced pressure environment.

21. *(Original)* The lithographic apparatus of Claim 15, wherein said conditioned chamber comprises a reduced particle concentration environment.